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TI - ~~Photosensitive resin compositions having end groups of~~

(methano)cyclohexene skeleton

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CODEN: JKXXAF

DT - Patent

LA - Japanese

IC - ICM C08F002/50

ICS C08F290/06;C09D4/02

CC - 37-6 (Plastics Manufacture and Processing)

Section cross-reference(s): 38

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| PATENT NO. | KIND | DATE | APPLICATION NO. | DATE |
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AB - The compns., useful for coatings, sealing materials, adhesives, binder etc., comprise (A) compds. having gtoreq.2 (/mol.) (methano)cyclohexene skeletons, (B) vinyl ether monomers, and (C) photopolymn. initiators, where gtoreq.1 of the (methano)cyclohexene moiety exists at mol. terminals of A. The compns. show excellent curability in air and provide cured products with good gloss and strong adhesion to supports. Thus, parts 3,6-methano-4-cyclohexene-1,2-dicarboxylic acid was reacted with OH-terminated polybutadiene (Poly bdr 45M) at 110.degree. in the presence of Et_3NCl to give a modified polybutadiene (A1), 50 parts of A1 was blended with 50 parts triethylene glycol divinyl ether and 3 parts Irgacure 261 to give a photocurable compn. The compn. was applied on glass substrate and lost surface tack upon 70 mJ/cm² UV exposure. The cured film of the compn. showed good adhesion to steels, plastics, and plywoods.

ST - methanocyclohexene terminated photosensitive compn coating binder; methanocyclohexenecarboxylic acid vinyl ether photosensitive compn; adhesion gloss tackfree property photosensitive compn

IT - Polymerization catalysts
(cationic, photochem.; photosensitive resin compns. having end groups of (methano)cyclohexene end groups)

IT - Butadiene rubber, preparation
RL: IMF (Industrial manufacture); PRP (Properties); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(hydroxy-terminated, Poly bdr 45M, reaction products with 3,6-methano-4-cyclohexene-1,2-dicarboxylic acid and triethylene glycol divinyl ether; photosensitive resin compns. having end groups of (methano)cyclohexene end groups)

IT - Light-sensitive materials
(photosensitive resin compns. having end groups of (methano)cyclohexene end groups)

IT - Polyimides, preparation
RL: IMF (Industrial manufacture); PRP (Properties); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(photosensitive resin compns. having end groups of (methano)cyclohexene end groups)

IT - Polyimides, preparation
Polyimides, preparation
Polyimides, preparation
RL: IMF (Industrial manufacture); PRP (Properties); TEM (Technical or

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Cl 1-2, 9, 10, 13, 17, 19, 24-29